

Supplementary Data

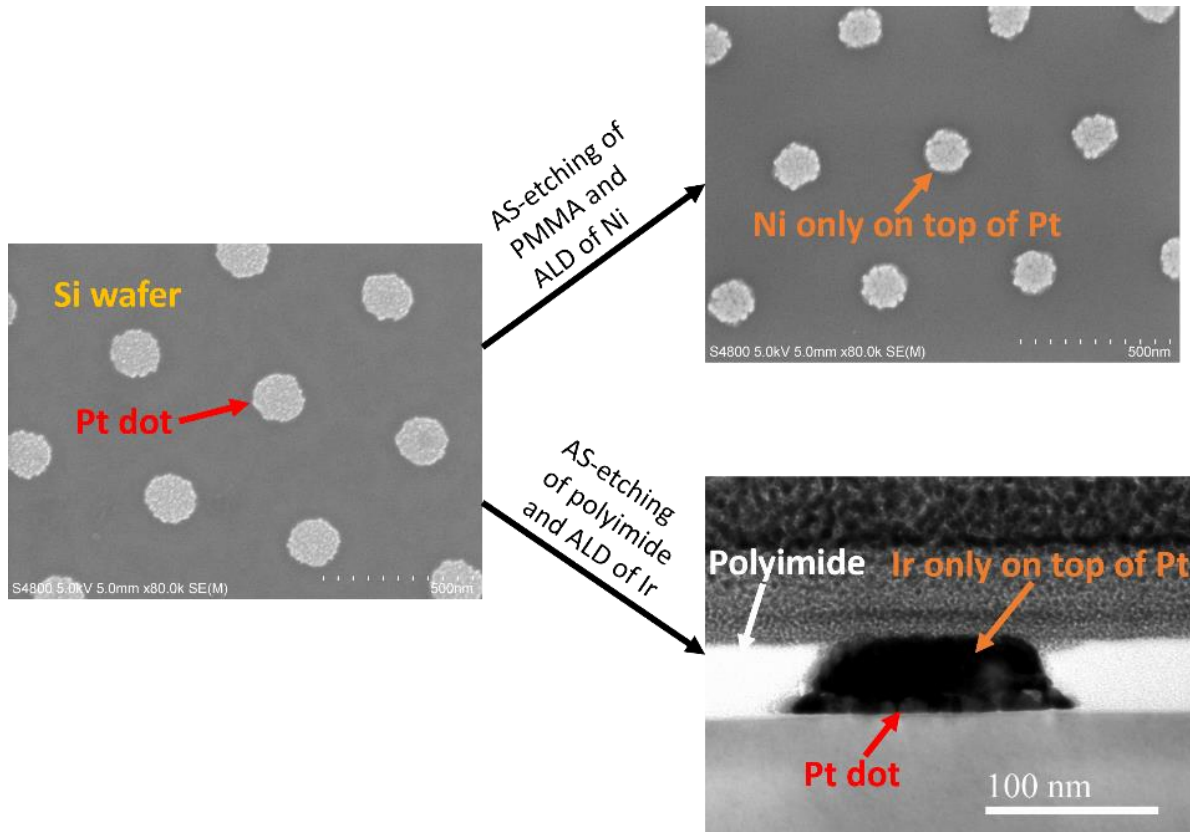


Fig. 1. SEM images of (left) patterned Pt/SiO₂ before the area-selective etching process and (top right) after the area-selective etching of PMMA followed by ALD of Ni and removal of PMMA. (bottom right) TEM image after the area-selective etching of polyimide followed by ALD of Ir without removing polyimide.

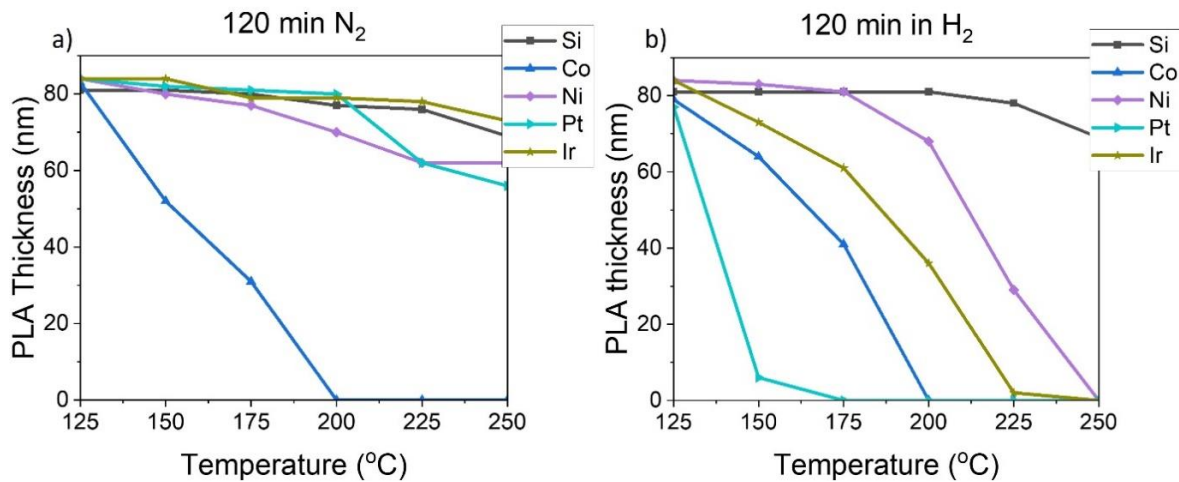


Fig. 2. Changes in the thicknesses of PLA thin films over temperature on different surfaces after 120 min in (a) N₂ atmosphere and (b) H₂ atmosphere.